

Abstract

METHOD AND APPARATUS FOR CALIBRATING MARKING POSITION IN CHIP SCALE MARKER

5 A method and apparatus for calibrating a marking position in a chip scale
marker are provided. The method includes: (a) placing a screen which is
equivalent in shape to the wafer on a wafer holder for holding the wafer; (b)
irradiating a laser beam at a predetermined target point on the screen, and
measuring the position of the laser beam by a camera being moved above the
target point; (c) transmitting the measured position information to a controller; (d)
10 repeating steps (b) and (c) at a plurality of predetermined points; (e) comparing
the transmitted position information with the target point; and (f) calibrating the
position of the laser beam irradiated on the wafer by adjusting mirrors of the
galvano scanner in the event that a deviation between the position information
and the target point falls beyond a predetermined value.

15
Figure 3

